

ABSTRACT

Resist compositions comprising as the base resin a
5 polymer using an alkoxyalkyl (meth)acrylate as a reactive
group which is decomposable under the action of an acid to
increase solubility in alkali have advantages including a
practical level of shelf stability, a significantly enhanced
contrast of alkali dissolution rate before and after
10 exposure, a high sensitivity, and a high resolution over a
wide baking temperature range. The compositions are best
suited as a chemically amplified positive resist material for
micropatterning in the manufacture of VLSI.